

Notice of References Cited

Application No.

09-887,289

Applicant(s)

Wurzen et al

Examiner

George Goudreau

Group Art Unit

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☆	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS
A	5885870	3-23-99	Maiti et al.	438	261
B	6,323,046	11-27-01	Agarwal	438	8
C					
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E					
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K					
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M					

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☆	DOCUMENT NO.	DATE	COUNTRY	NAME	CLASS	SUBCLASS
N	05-283679	10-29-93	Japan	Kusunoki et al		
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R						
S						
T						

NON-PATENT DOCUMENTS

☆	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
U	"Furnace Nitridation of Thermal Silica In Pure Nitrogen Oxide Ambient For ULSI MOS Applications"; IEEE Electron Device Letters (1992), 13(2); pp. 117-119; AAn et al.	
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* A copy of this reference is not being furnished with this Office action.
(See Manual of Patent Examining Procedure, Section 707.05(a).)